Canadian Association of Physicists

Association canadienne des physiciens et physiciennes

Contribution ID: **331** Type: **Poster (Non-Student) / Affiche (Non-étudiant(e))**

POS-B7 – Optical Emission Interferometry for Monitoring of Plasma Processes

Wednesday 9 June 2021 13:49 (2 minutes)

We present our simple and cost-efficient setup for real-time monitoring of substrate thickness in plasma etching/deposition processes. Thin film interference occurs as light from the plasma passes through the substrate material, by observing the cycles of peaks and troughs in the intensity, the rate of etching/deposition was obtained.

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Session Classification: W-POS-B #5-8 Poster session (DPP) / Session d'affiches (DPP)

Track Classification: Symposia Day (DPP) - Low temperature plasmas/Fusion plasmas (magnetic and inertial confinement)/ Laser plasmas/Basic plasmas